ISPlasma is specialized international symposium where more than 1,000 world-leading scientists and engineers can get together in the Tokai region (central Japan) to discuss latest researches in the fields of advanced plasma science, its application for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. We aim that holding this symposium series will establish an advanced plasma science and technology center in Tokai region which can collaborate with research institutes worldwide.

Related Fields

PLASMA SCIENCE

- Plasma Source
- Modeling and Simulation
- Thin Film Deposition Process
- Plasma Biology and Medicine
- Plasma for Nanotechnology
- Advanced Plasma Measuring Technology
- Etching Process
- Flexible Electronics
- Plasma for Clean Energy

NITRIDE SEMICONDUCTORS

- Crystal Growth of GaN and Related Materials
- Characterization
- Optical Devices
- MBE Growth of Nitrides
- Device Processing
- Electron Devices

NANOMATERIALS

- Nanocarbon Materials
- Surface Modification/Surface Functionalization
- Nanoparticles/Nanowires/Nanorods
- Porous Materials
- Composite/Functionally Grade Materials
- Nanomaterials for Energy Applications

JJAP Special Issue

Selected papers will be published in a Special Issue of Jpn. J. Appl. Phys. (JJAP).
Submission Deadline: Feb. 28 (Thu), 2013

Award

Date : Feb. 1 (Fri), 16:45-
Place : Toyoda Auditorium, Nagoya Univercity
"ISPlasma 2013 Awards" will be given to outstanding papers.

Exibition

ISPlasma 2013 will provide a valuable opportunity for all the related professionals to showcase their technology and products.
Date: Jan. 29 (Tue) to Feb. 1 (Fri)

Tutorials

Tutorials for Plasma Science, Nitride Semiconductors and Nanomaterials will be run on Jan. 28 (Mon)

Networking Events

- **Welcome Party**
  Date : Jan. 28 (Mon), 6:00 pm -
  Place : Noyori Conference Hall, Nagoya University
- **Banquet**
  Date : Jan. 30 (Wed), 7:00 pm -
  Place : South Cafeteria, Nagoya University
  Fee : General JPY 5,000 / Student JPY 2,000
  *Banquet fees must be paid at the time of registration.

Related Conference

The 6th International Conference on Plasma Nanotechnology and Science (IC-PLANTS 2013)
Date : Feb. 2-3, 2013
Venue: Gero Synergy Center, Gero city, Gifu
URL : http://www.plasma.engg.nagoya-u.ac.jp/IC-2013/

Registration

Please register on our website.

Registration Fee

*Refunds for registration or banquet cannot be made at any reason.

	General	Student
Early Registration (before December 27, 2012 11:00 am, JST)	**JPY 20,000**	**JPY 3,000**
Late Registration (until January 17, 2013 11:00 am, JST)	**JPY 25,000**	**JPY 5,000**
On-Site Registration	**JPY 30,000**	**JPY 7,000**
Banquet Fee (on January 30, 2013)	**JPY 5,000**	**JPY 2,000**

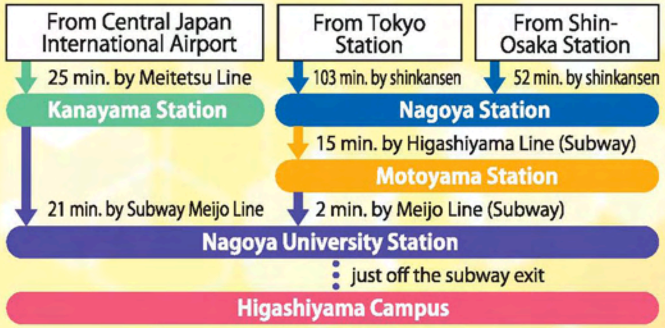
For those attending "Industry-Academia-Government Collaboration Lectures and Panel Discussion" (Jan. 30) only : **Registration Fee is FREE**

Schedule at a glance

Jan. 28 (Mon)	Tutorial Session Welcome Party at Noyori Conference Hall, Nagoya University
Jan. 29 (Tue)	Opening Plenary Lecture: Hideo Ohno (Tohoku University, JAPAN) Technical Session Poster Session
Jan. 30 (Wed)	Technical Session Poster Session Panel Discussion "How We Fire up the Innovation Engine? -Toward the Establishment of Global Innovation Research Cluster-" Banquet at South Cafeteria, Nagoya University
Jan. 31 (Thu)	Technical Session Poster Session Panel Discussion "Perspective of Nitride Semiconductors -The Role of Plasma Science and Nano Technology-"
Feb. 1 (Fri)	Technical Session Poster Session Panel Discussion "Towards Smart Energy Cities" Award Closing

Venue

Nagoya University (Higashiyama Campus)
Furo-cho, Chikusa-ku, Nagoya, 464-8601, Japan
TEL:+81-(0)52-789-5111


From Central Japan International Airport
25 min. by Meitetsu Line
Kanayama Station
21 min. by Subway Meijo Line
From Tokyo Station
103 min. by shinkansen
From Shin-Osaka Station
52 min. by shinkansen
Nagoya Station
15 min. by Higashiyama Line (Subway)
Motoyama Station
2 min. by Meijo Line (Subway)
Nagoya University Station
just off the subway exit
Higashiyama Campus

MEXT (Ministry of Education, Culture, Sports, Science and Technology)
Program for Fostering Regional Innovation (Global Type)
-Tokai Region Nanotechnology Manufacturing Cluster-

ISPlasma2013

5th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials

January 28 - February 1, 2013
Nagoya University, Japan

Organizing Committee

Chairperson

Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University

Vice-Chairperson

Hideki Masuda, Nagoya Institute of Technology
Keiji Nakamura, Chubu University
Mineo Hiramatsu, Meijo University

Sponsored by :
Aichi Science & Technology Foundation,
ISPlasma2013 Organizing Committee

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Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research, The Japanese Association for Crystal Growth

Grants :
Support Center for Advanced Telecommunications Technology Research, Foundation, Foundation for Promotion of Material Science and Technology of Japan, The Murata Science Foundation, DAIKO FOUNDATION

Contact

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E-mail: isplasma@congre.co.jp

http://www.isplasma.jp/

ISPlasma2013

JAN 28 MON

TUTORIAL SPEAKERS

PLASMA SCIENCE

L. Overzet (The University of Texas at Dallas, USA)
K. Sasaki (Hokkaido University, JAPAN)

NITRIDE SEMICONDUCTORS

J. Duboz (CRHEA-CNRS, FRANCE)
Y. Nanishi (Ritsumeikan Univ., JAPAN/Seoul National Univ., KOREA)

NANOMATERIALS

F. Fracassi (University of Bari, ITALY)
S. Iijima (Meijo University, JAPAN)

JAN 29 TUE

PLENARY SPEAKER

Hideo Ohno (Tohoku University, JAPAN)

KEYNOTE SPEAKERS

PLASMA SCIENCE

J. G. Han (Sungkyunkwan University, KOREA)

NANOMATERIALS

R. Ruoff (The University of Texas at Austin, USA)

ADVANCED CARBON MATERIALS

Focused Session

Y. Lee (Sungkyunkwan University, KOREA)

ADVANCED NITRIDE SEMICONDUCTORS

Focused Session

N. Grandjean (EPFL, SWITZERLAND)

ENERGY REVOLUTION

Focused Session

T. Nozaki (Tokyo Institute of Technology, JAPAN)
L. Shaw (Illinois Institute of Technology, USA)

INDUSTRY-ACADEMIA-GOVERNMENT COLLABORATION

Focused Session
Simultaneous Interpretation

P. Feraboli (Automobili Lamborghini Laboratory at the University of Washington Seattle, USA)
S. Fujimura (Tokyo Institute of Technology, JAPAN)
E. Yamaguchi (Doshisha University, JAPAN)

INVITED SPEAKERS

PLASMA SCIENCE

P. Chabert (LPP, CNRS Ecole Polytechnique, FRANCE)
U. Czarnetzki (Ruhr University Bochum, GERMANY)
J. Duh (National Tsing-Hua University, TAIWAN)
A. Eppler (Lam Research Corporation, USA)
A. Fridman (Drexel University, USA)
M. C. M. Van de Sanden (Dutch Institute for Fundamental Energy Research, THE NETHERLANDS)

NITRIDE SEMICONDUCTORS

R. Dwiliński (Ammono Company, POLAND)
T. Fujiwara (ROHM Co., Ltd., JAPAN)
E. Monroy (CEA-Grenoble, FRANCE)
M. Pristovsek (University of Cambridge, UK)
P. Ruterana (CIMAP, UMR 6252, CNRS, ENSICAEN, CEA, FRANCE)
W. Walukiewicz (Lawrence Berkeley National Laboratory, USA)

NANOMATERIALS

J. Cheng (IBM Almaden Research Center, USA)
H. Kwon (EMPA, Switzerland)
I. Lee (Chonbuk National University, KOREA)
C. Liu (Tianjin University, CHINA)
M. Nakayama (Nagoya Institute of Technology, JAPAN)
T. Wei (Chung-Yuan University, TAIWAN)

ADVANCED CARBON MATERIALS

Focused Session

S. Yamasaki (AIST, JAPAN)

ADVANCED NITRIDE SEMICONDUCTORS

Focused Session

K. Chen (The Hong Kong University of Science and Technology, CHINA)
B. Daudin (CEA-Grenoble, FRANCE)
H. Fujioka (Institute of Industrial Science, The University of Tokyo, JAPAN)
T. Kikkawa (FUJITSU LABORATORIES LTD., JAPAN)

ENERGY REVOLUTION

Focused Session

I. Mukhopadhyay (Pandit Deendayal Petroleum University, INDIA)
Y. Nishikitani (JX Nippon Oil & Energy Corporation, JAPAN)

PANEL DISCUSSION

January 30 WED

How We Fire up the Innovation Engine?
-Toward the Establishment of Global Innovation Research Cluster-

Simultaneous Interpretation

<Moderator>
S. Fujimura (Tokyo Institute of Technology, JAPAN)
<Panelist>
P. Feraboli (Automobili Lamborghini Laboratory at the University of Washington Seattle, USA)
E. Yamaguchi (Doshisha University, JAPAN)
M.Hori (Nagoya University, JAPAN)
To be announced

*Attendees of this session ONLY: Free of charge

January 31 THU

Perspective of Nitride Semiconductors
– The Role of Plasma Science and Nano Technology –

Focused Session

<Moderator>
O. Oda (Nagoya Institute of Technology, JAPAN)
<Panelists>
K. Chen (The Hong Kong University of Science and Technology, CHINA)
B. Daudin (CEA-Grenoble, FRANCE)
H. Fujioka (Institute of Industrial Science, The University of Tokyo, JAPAN)
N. Grandjean (EPFL, SWITZERLAND)
H. Kano (NU EcoEngineering CO., LTD., JAPAN)
T. Kikkawa (FUJITSU LABORATORIES LTD., JAPAN)
I. Lee (Chonbuk National Univercity, KOREA)
Y. Nanishi (Ritsumeikan Univ., JAPAN/Seoul National Univ., KOREA)
M. Pristovsek (University of Cambridge, UK)

February 1 FRI

Towards Smart Energy Cities

Focused Session

<Moderator>
T. Nozaki (Tokyo Institute of Technology, JAPAN)
<Panelists>
T. Matsumoto (Osaka Gas Co., Ltd., JAPAN)
I. Mukhopadhyay (Pandit Deendayal Petroleum University, INDIA)
M. Nakayama (Nagoya Institute of Technology, JAPAN)
Y. Nishikitani (JX Nippon Oil & Energy Corporation, JAPAN)
L. Shaw (Illinois Institute of Technology, USA)
W. Walukiewicz (Lawrence Berkeley National Laboratory, USA)

*Program and speakers listed above may change.
*Listed in alphabetical order.
*For detailed program, please visit our website.